

Status of the Gallium Nitride High Electron Mobility Transistor Radiation Testing for the NEPP Program

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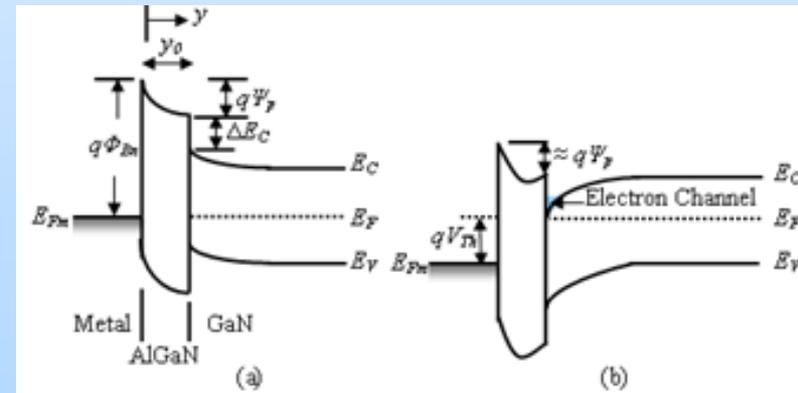
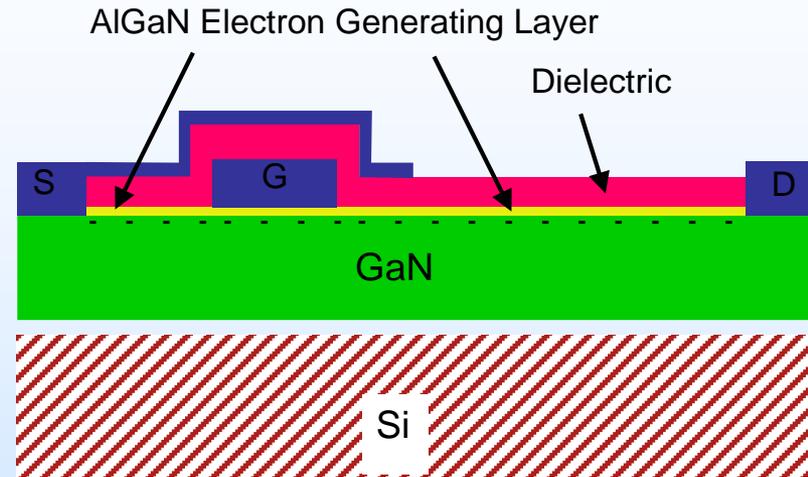


Current activities

- **Working group discusses best methods for evaluating new wide band gap technologies for infusion into space**
 - GRC, JPL, JSC, GSFC, AFRL
 - Monthly meeting to share data and resources for radiation effects testing and reliability analyses
- **Previous efforts have been broad stroke testing**
 - Heavy ion testing
 - Gallium Nitride HEMTs (JPL)
 - Silicon Carbide MOSFETs (GSFC)
 - Reliability screening
 - Temperature cycling of GaN and SiC
- **On going and future efforts**
 - Continues radiation testing and analysis
 - Reliability test screens for new devices
 - Guidelines for implementation and testing

GaN Basics

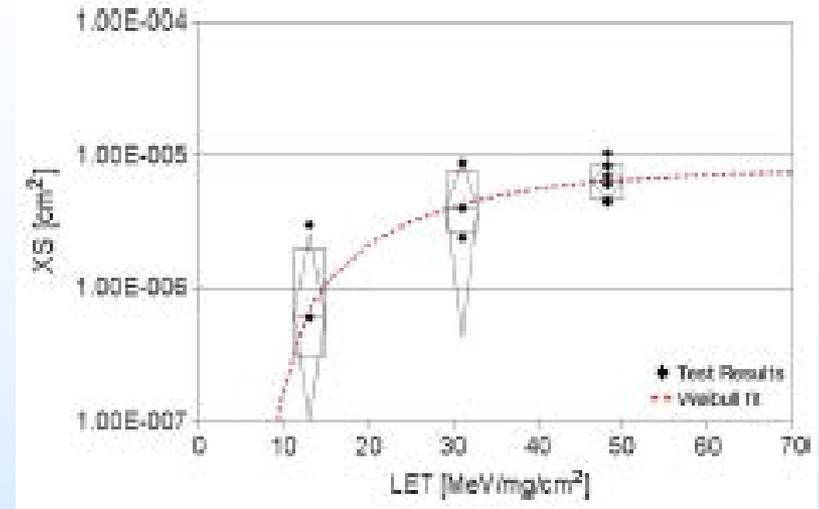
- **Current silicon power solutions are at their innate limits for space applications**
 - Silicon devices are at efficiency limit
 - Best hi-rel devices are less than ~400 V drain-to-source
- **GaN devices are becoming available**
 - Reliability effects are a concern
 - Gate stress is limited (abs max of $V_{gs} +6, -5$ V)
 - Thermal effects and aging are under study at GRC



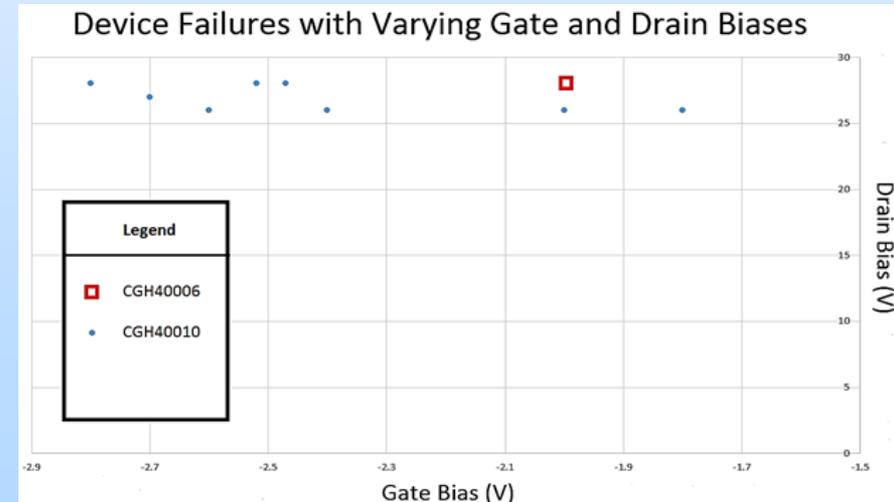
Destructive SEE have been seen in GaN HEMTs- RF GaN



- GaN substrate directly under gate experiences greatest electric field
 - Where 2DEG is reduced
- High electrical stress will exacerbate SEE
- SEE seen in RF devices
 - Tested in amplifier circuits
 - Depletion mode devices



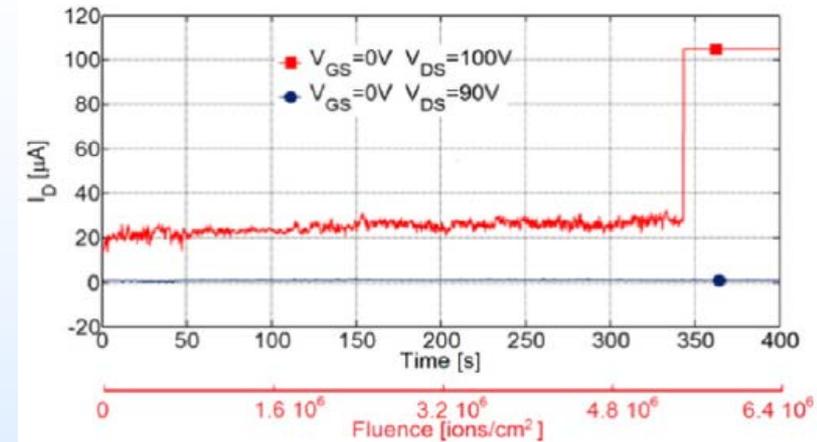
M. Rostewitz / Trans. Nucl. Sci, 2013



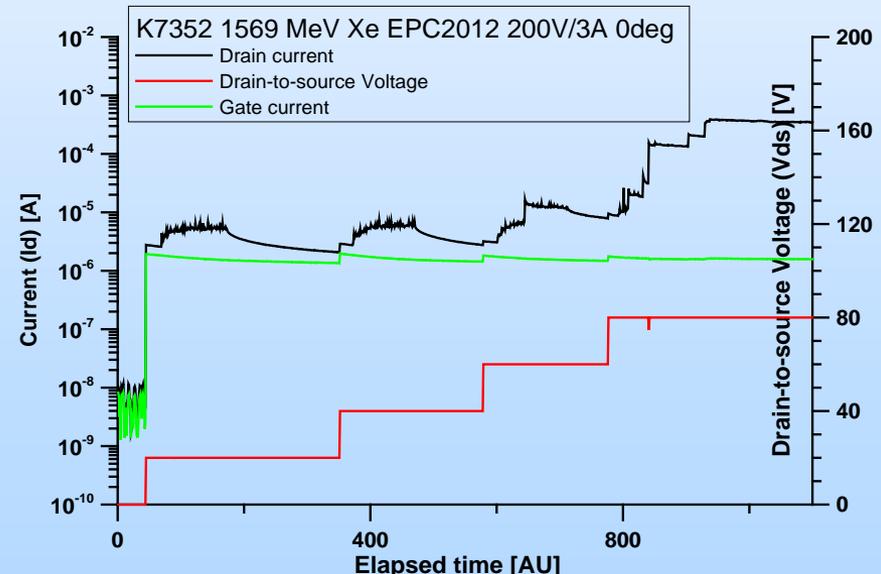
Destructive SEE have been seen in GaN HEMTs- eGaN



- Failure seen in 200 V eGaN from 40 V to 200 V
- A. Lidow et al / Trans. Nucl. Sci, 2014 did not observe
- Process variation or test interaction is suspected
- TID and DD are not issues



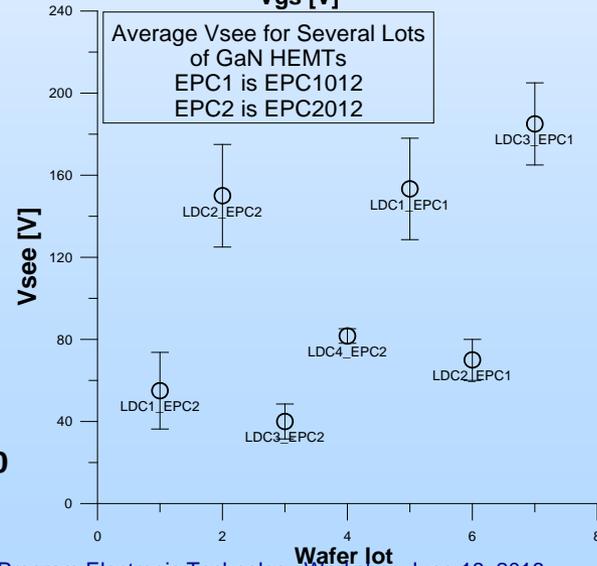
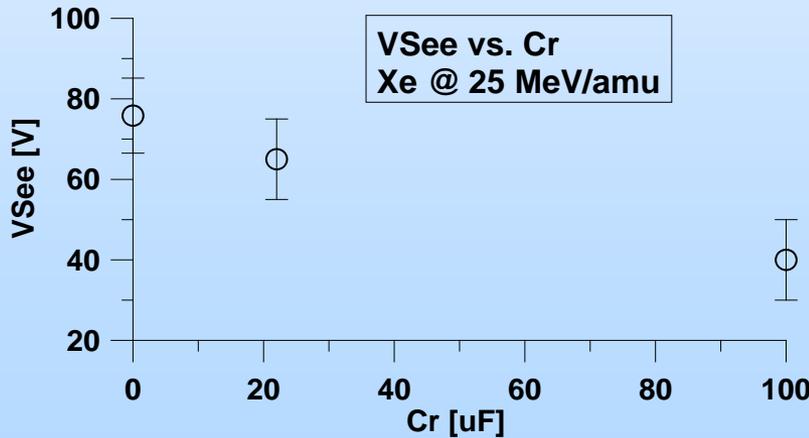
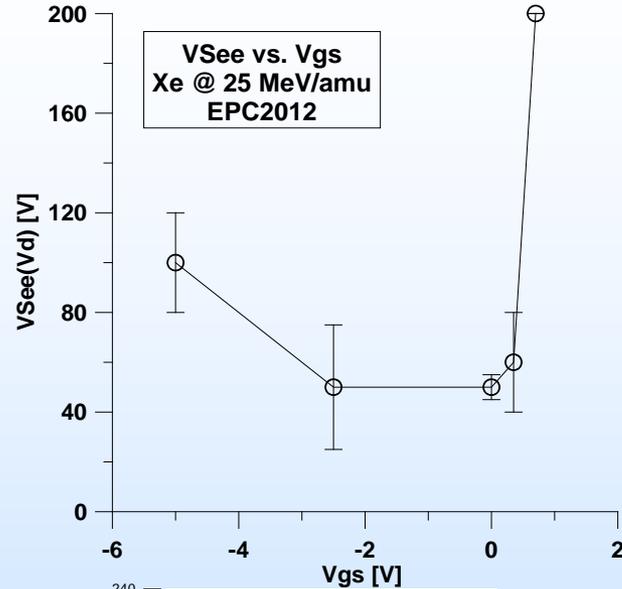
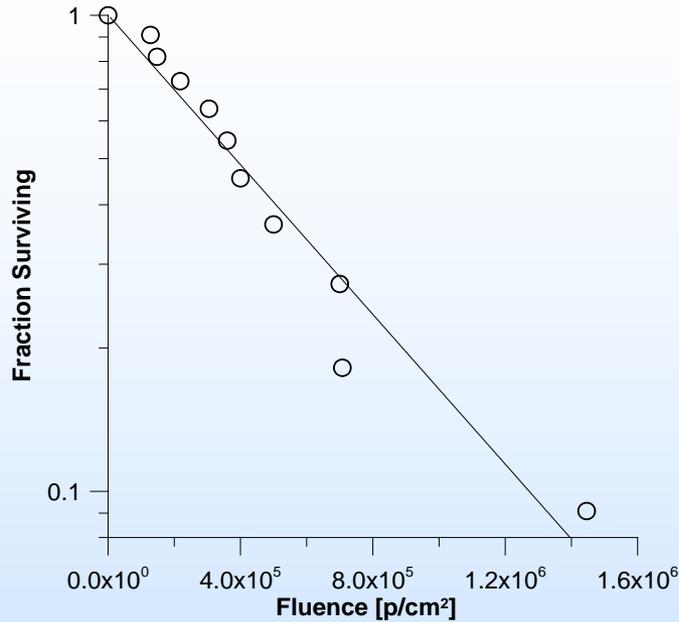
C. Abbate et al. / Microelectronics Reliability 55 (2015) 1496–1500



L. Scheick / Trans Nucl Sci (2014) 1296–1300



SEE in GaN are Very Complicated



Effect of Test Circuit on V_{SEE}

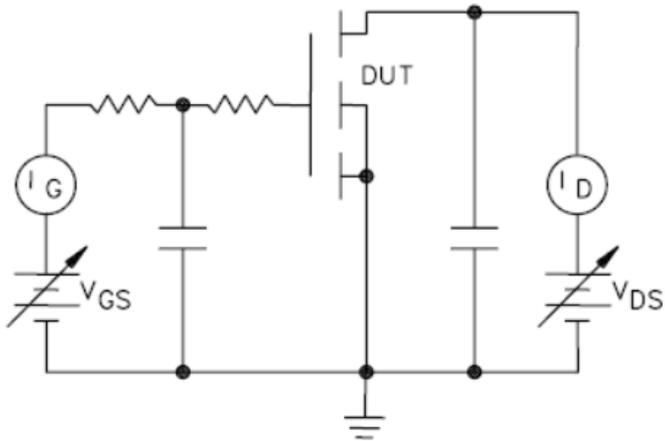
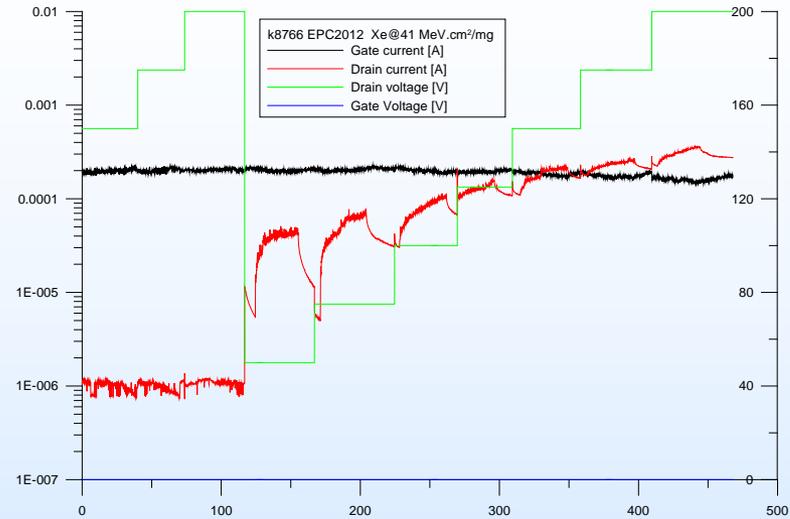
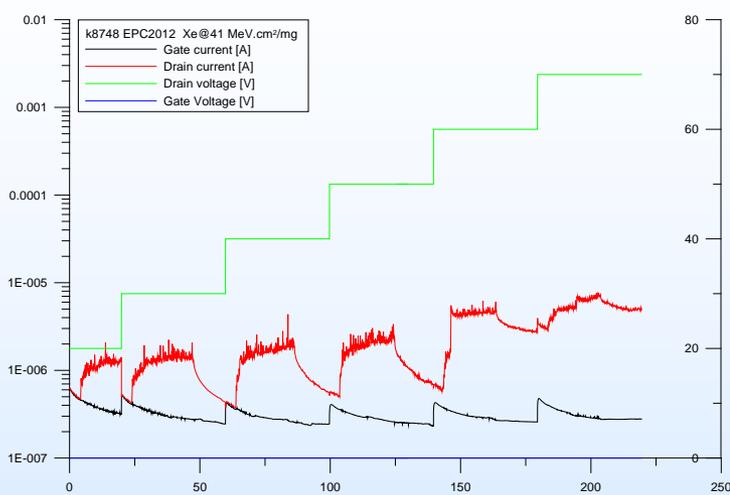
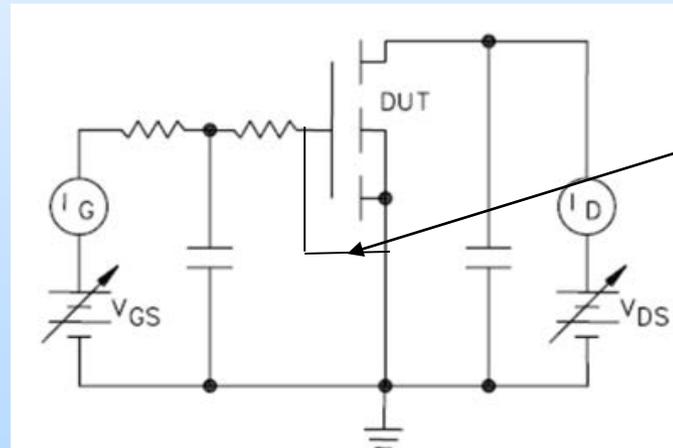


FIGURE 1080-1. Basic SEB/SEGR test circuit.

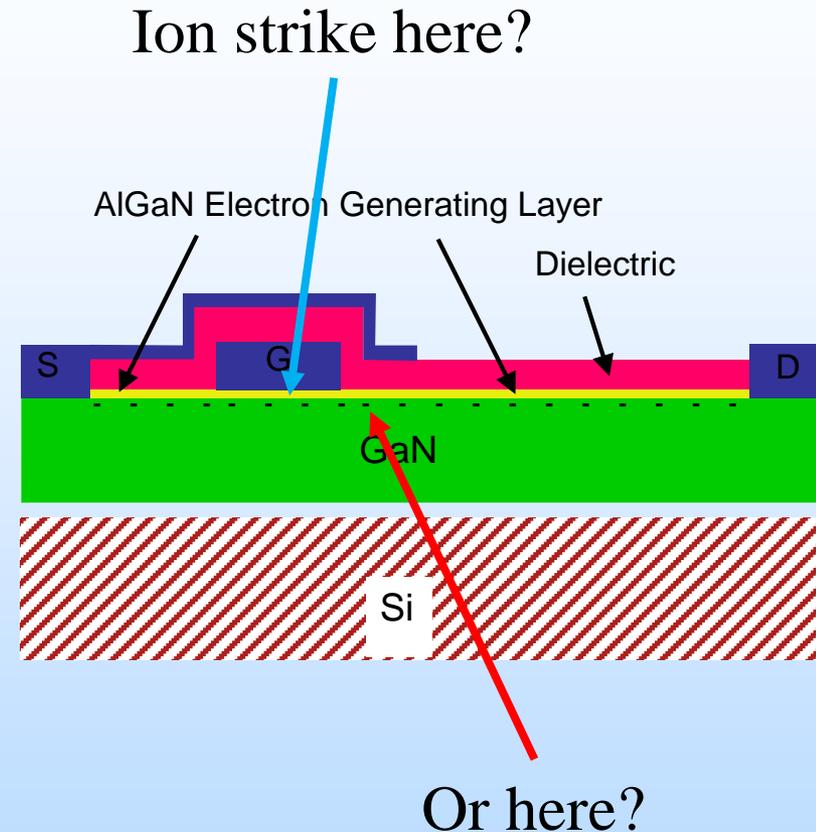


Shorted
gate to
source

FIGURE 1080-1. Basic SEB/SEGR test circuit.

Work to be done

- **Identification of SEE mechanism**
- **Establishment of SEE operating area**
- **Affect of local circuit on onset of SEE**
 - Similar to SEB in power
 - Parameterization of test circuits
- **Angular Effects**
 - Devices are lateral, and some effects have been seen





PGA26E19BA

TESTING OF PANASONIC PARTS

Optical Images

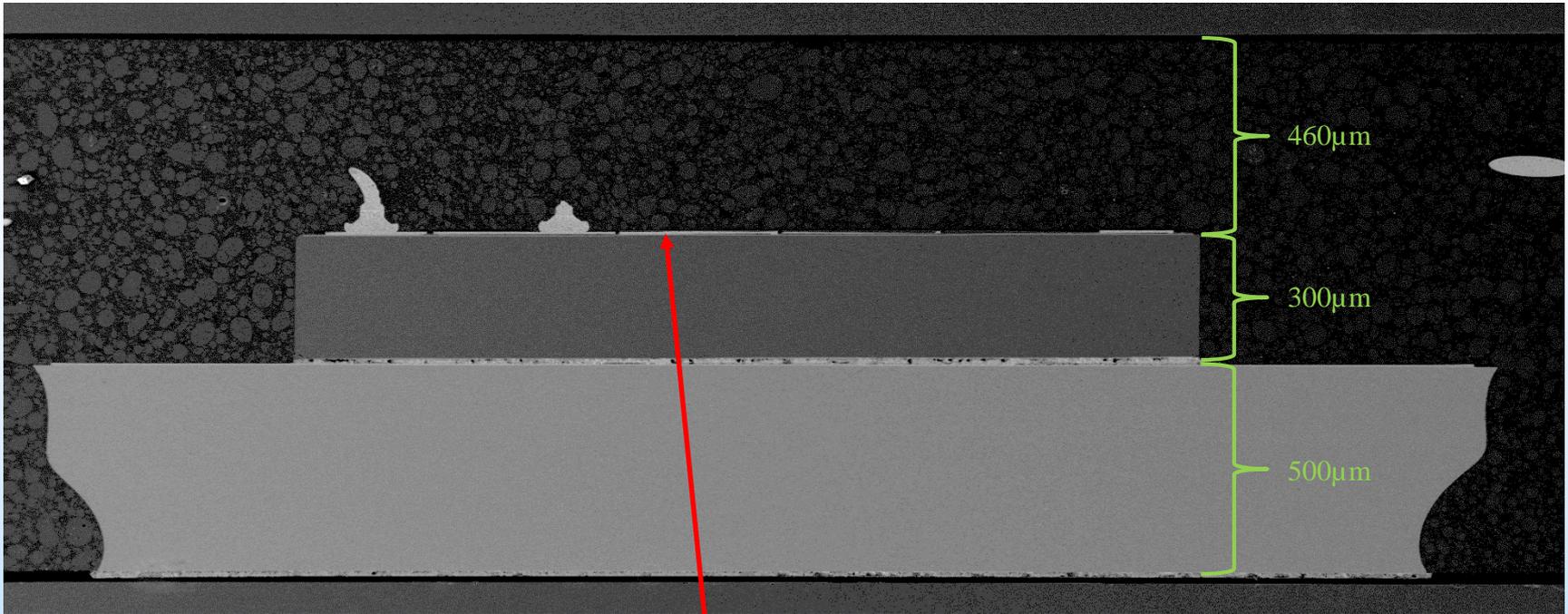


Front



Back

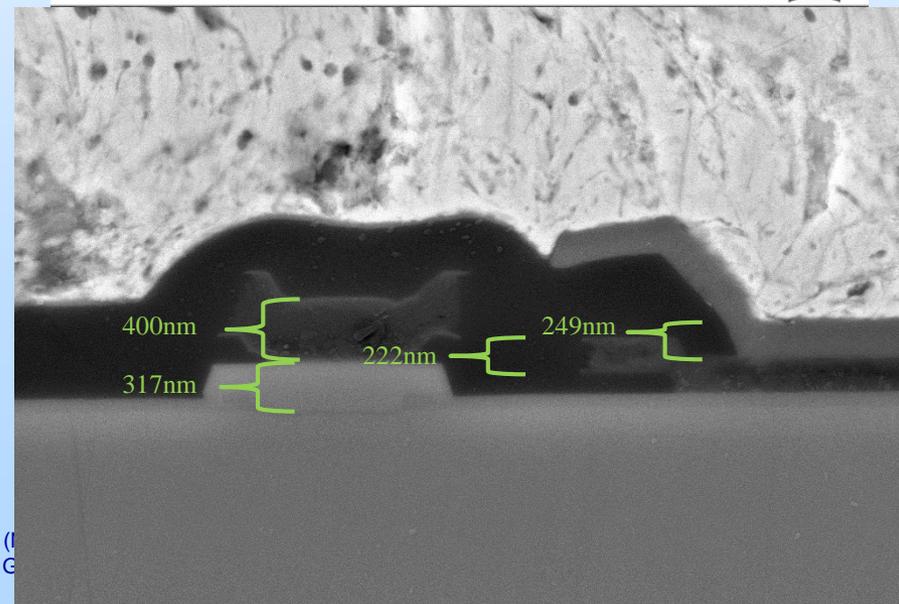
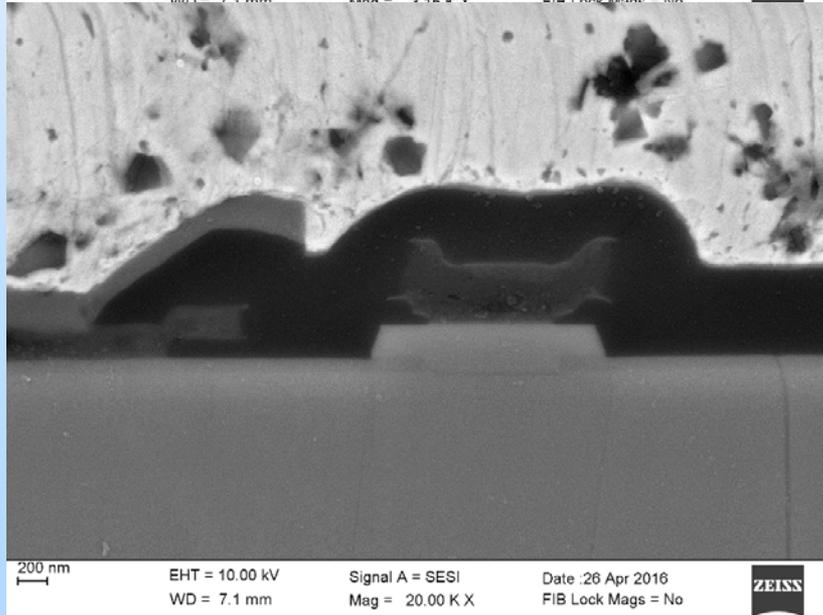
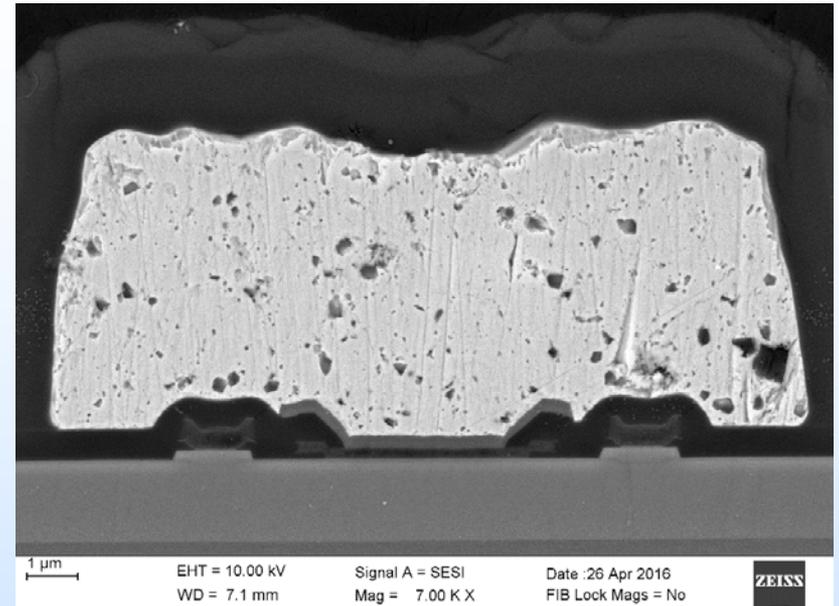
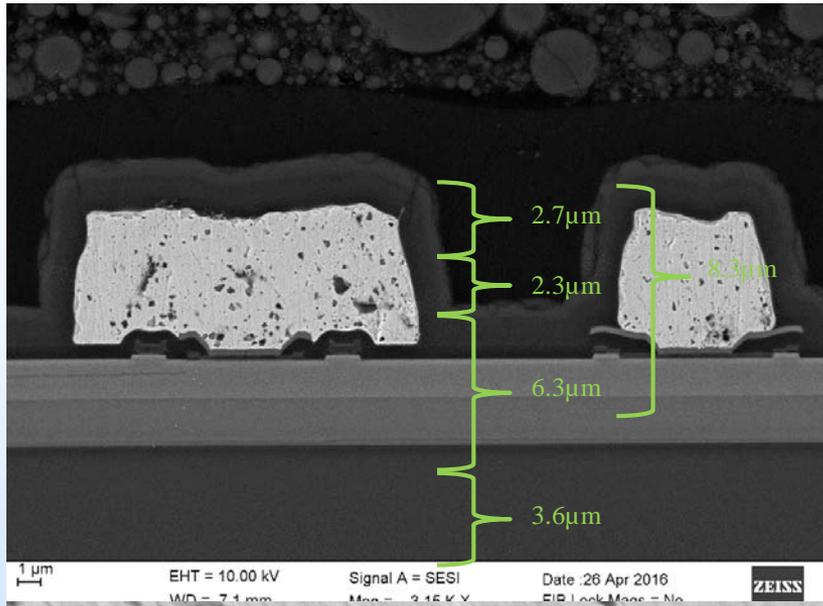
Package Cross Section Overview



The active region is very thin.

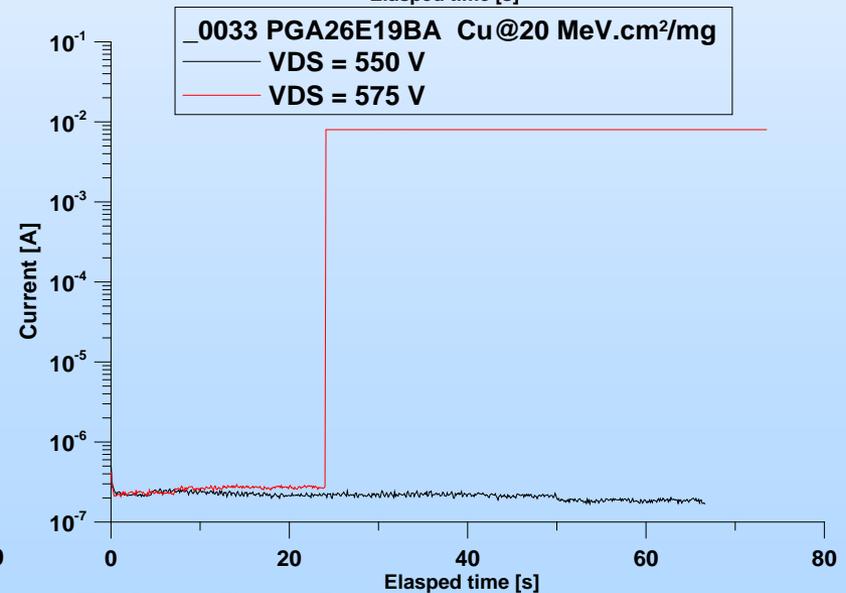
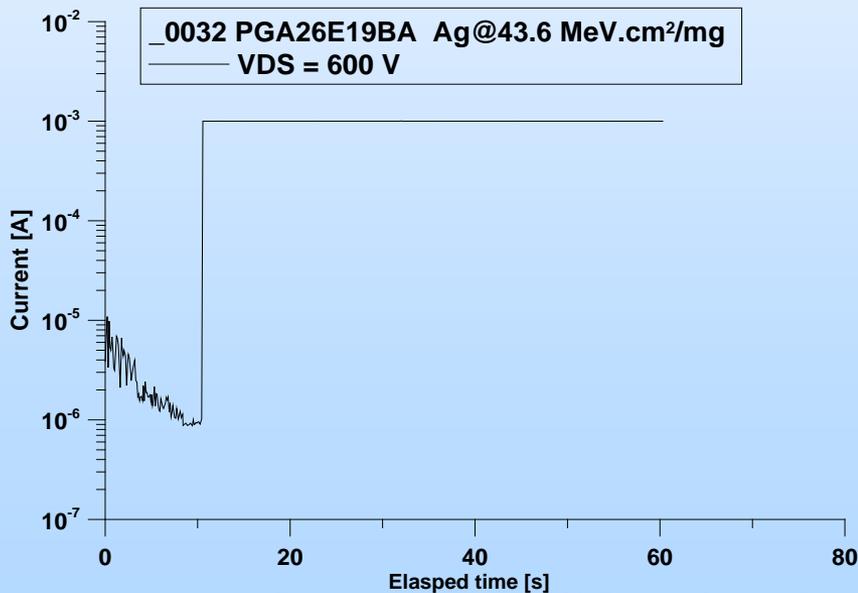
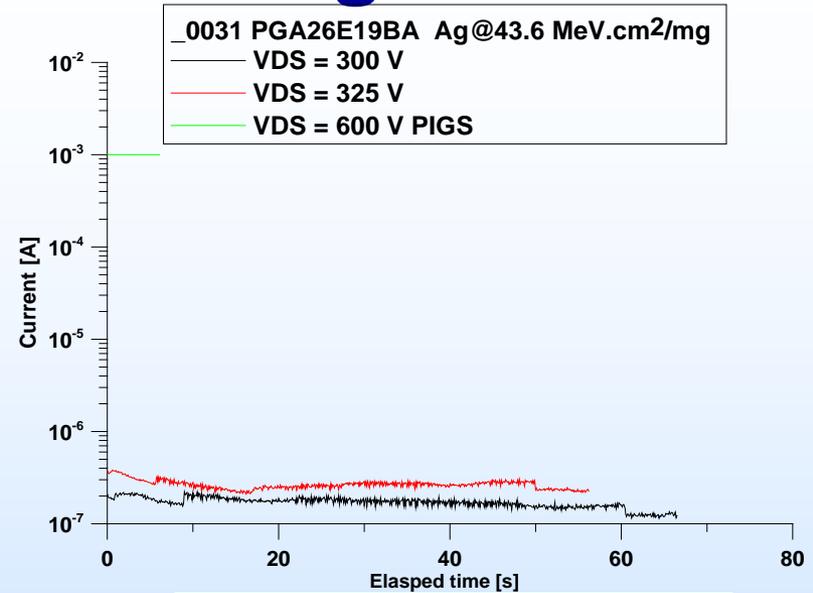
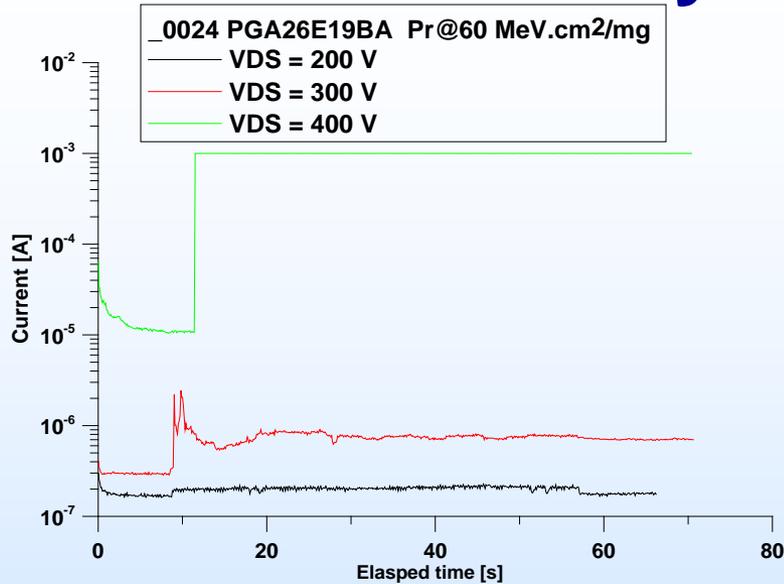


Cross Section Perpendicular to Gate



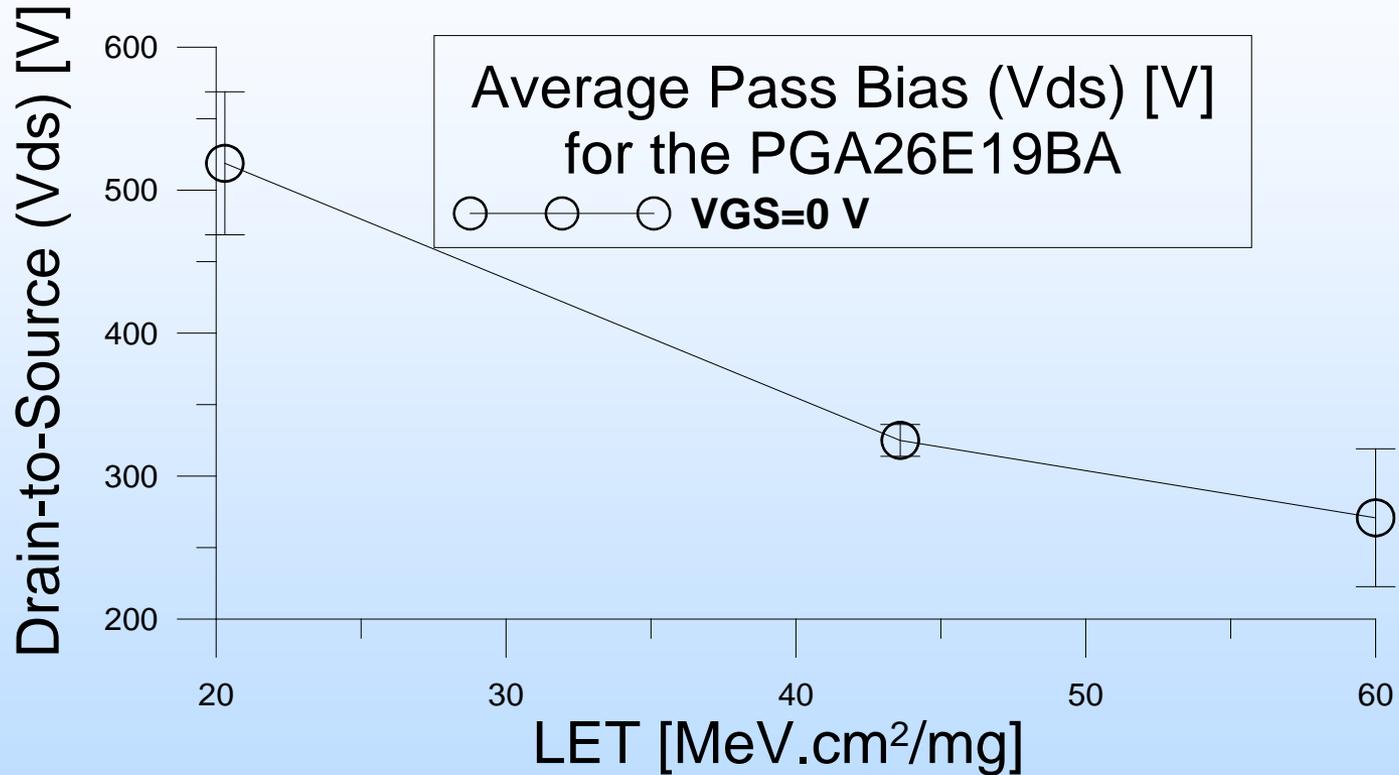


Heavy Ion Testing





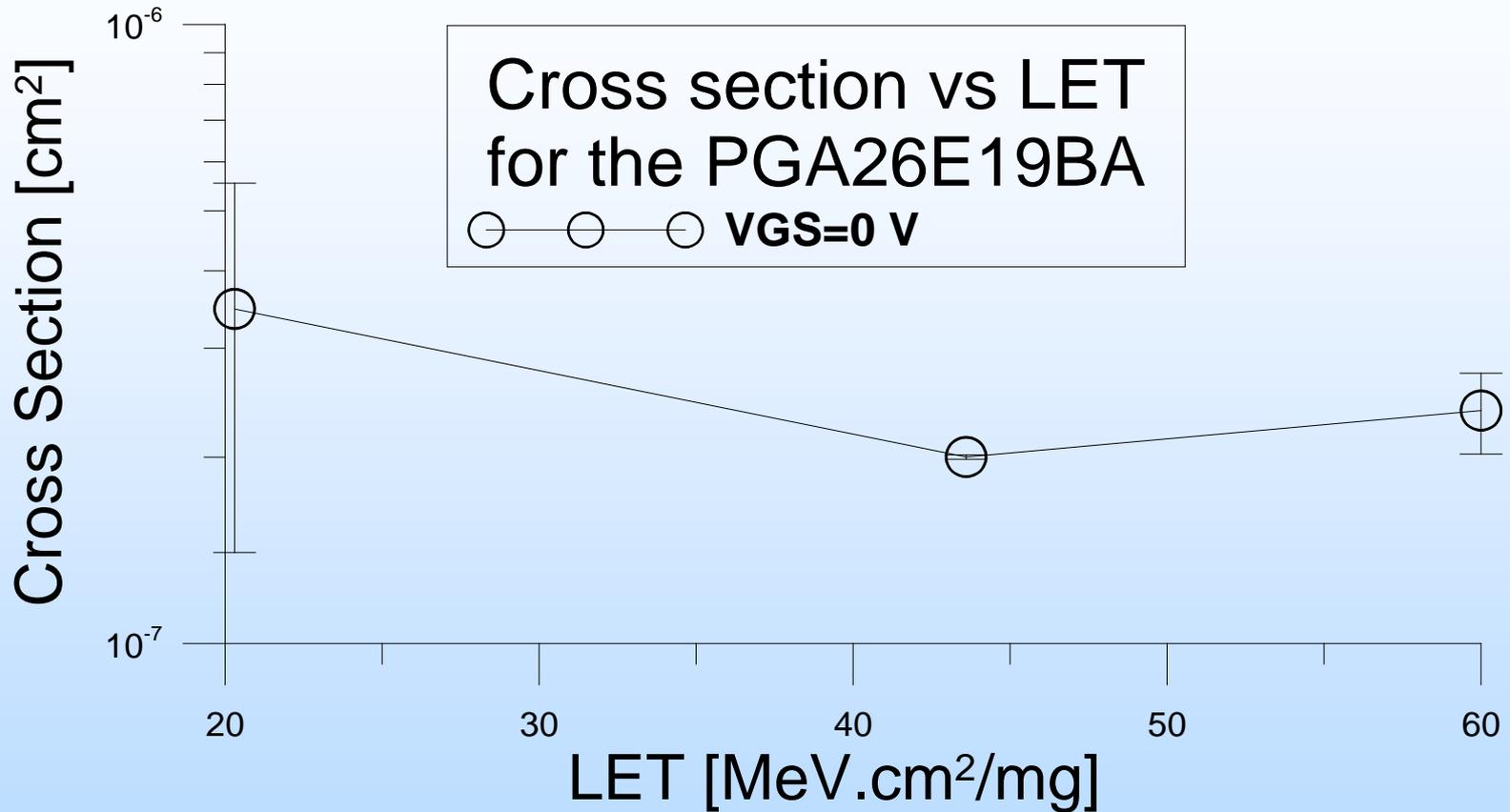
V_{SEE} as a Function of LET



Higher LET results in lower SEE Vds.



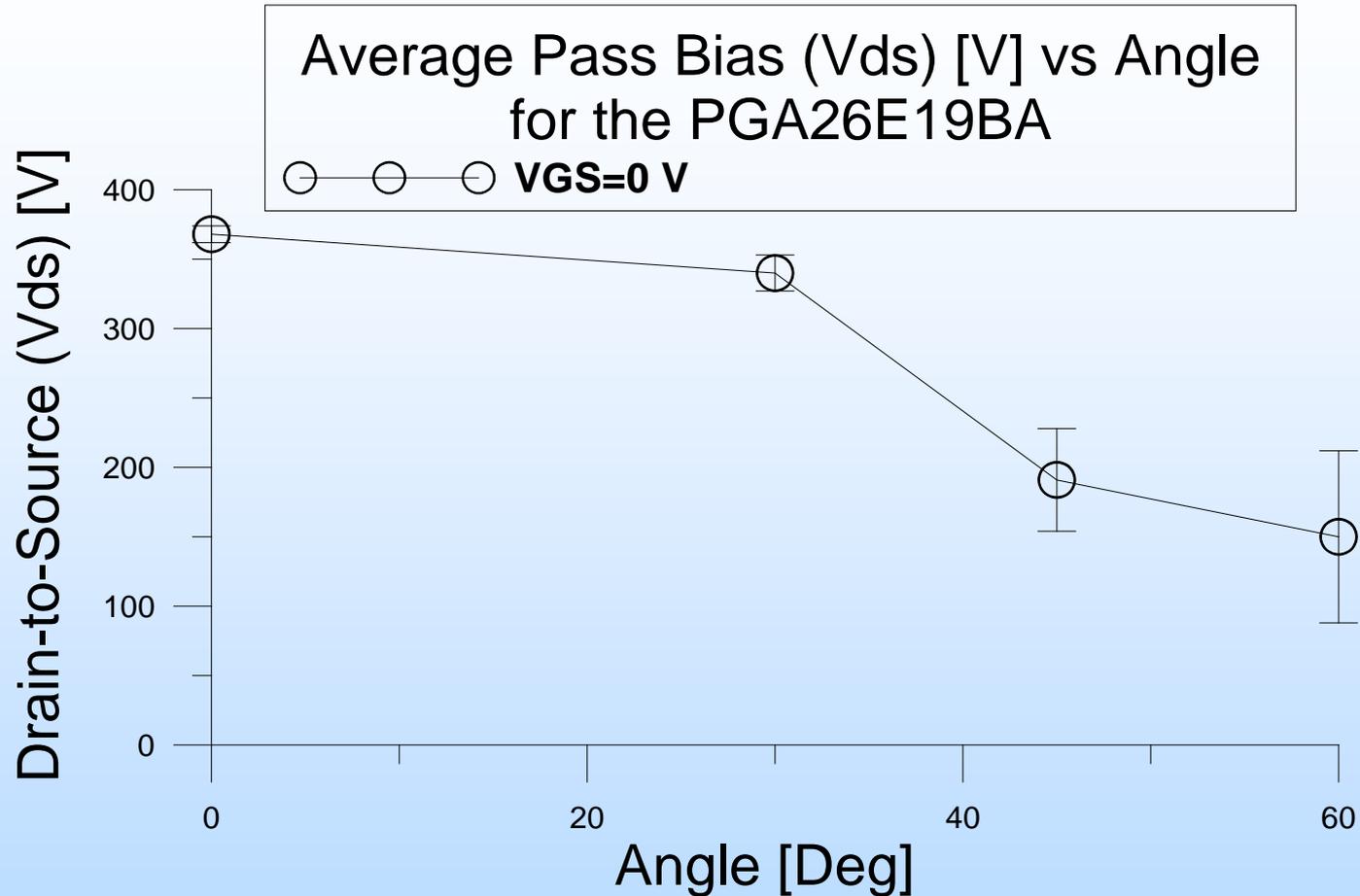
Cross-section as a Function of LET



Preliminary: Cross-section not dependent on LET.



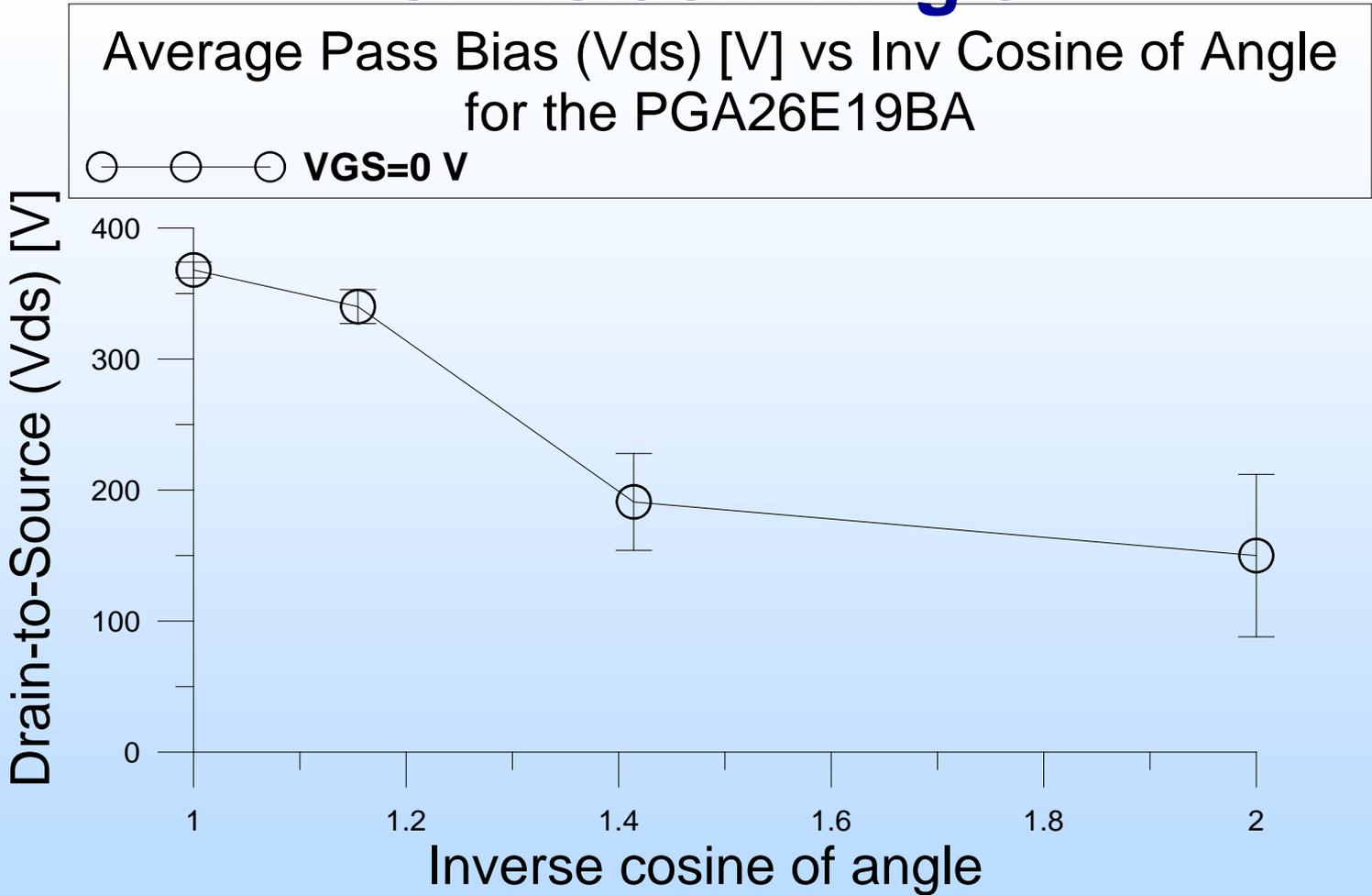
VSEE as a Function of Incident Angle



Lateral devices like this HEMT are expected to have an angular dependence.



VSEE as a Function of Inverse Cosine of Incident Angle



SEE Vds has a strong angular response.



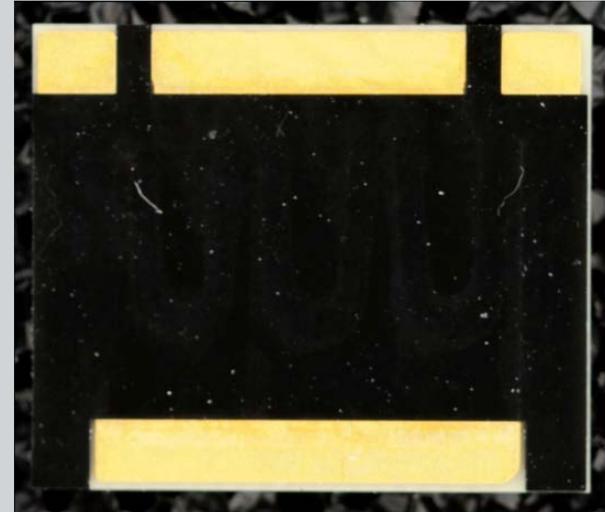
GS66516T

TESTING OF GANSYSTEMS PARTS

Optical Images

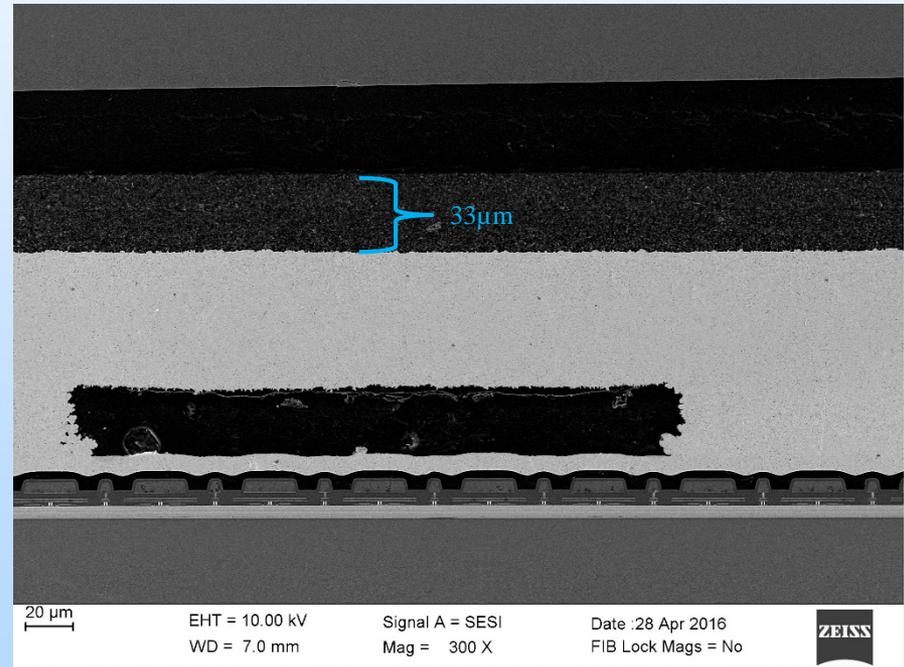
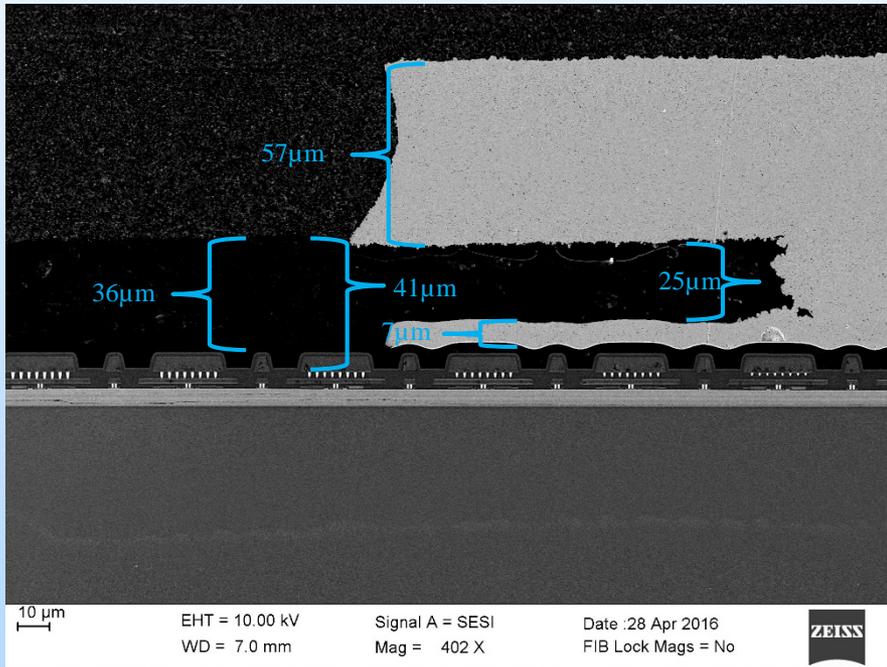
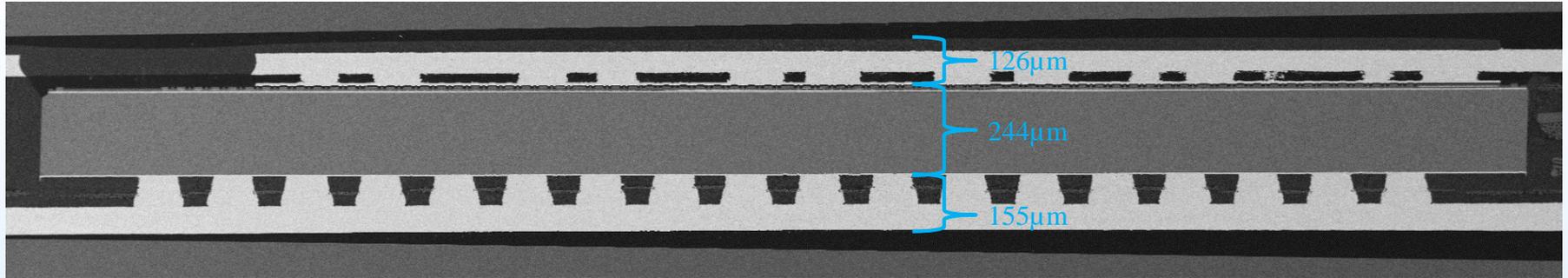


Front

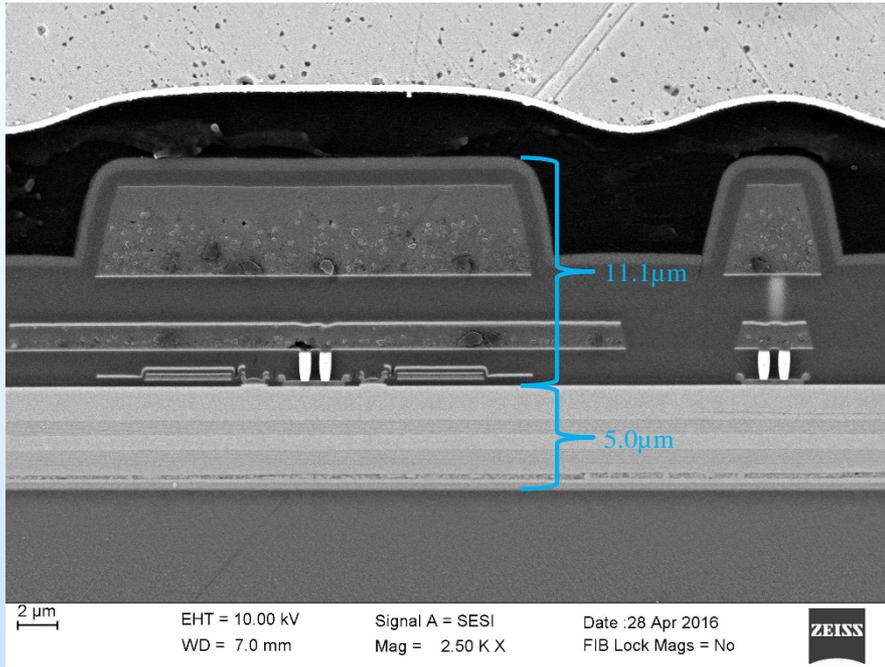


Back

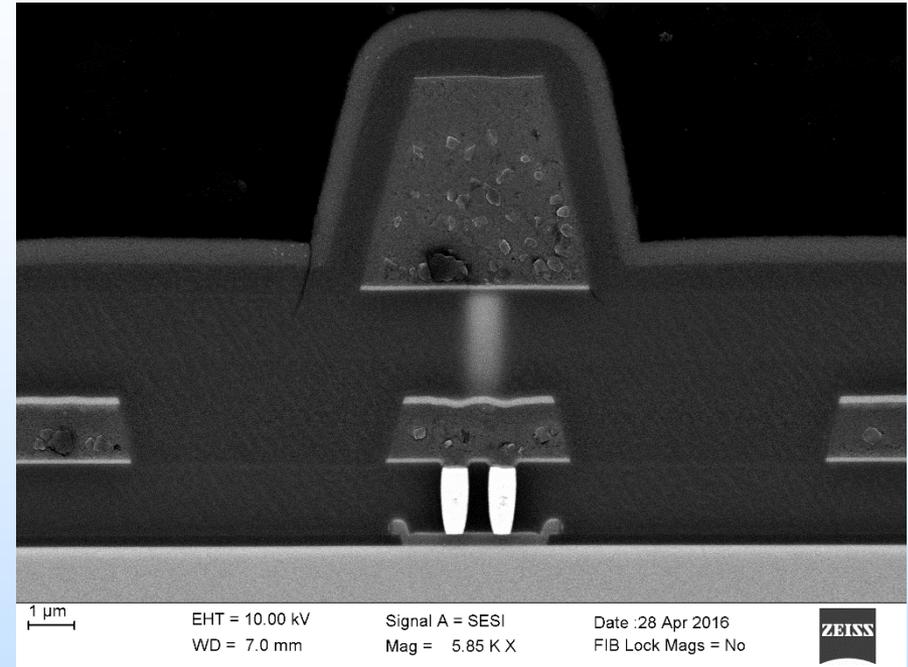
Package Cross Section Overview



Cross Section Perpendicular to Gate



Active contacts and gates

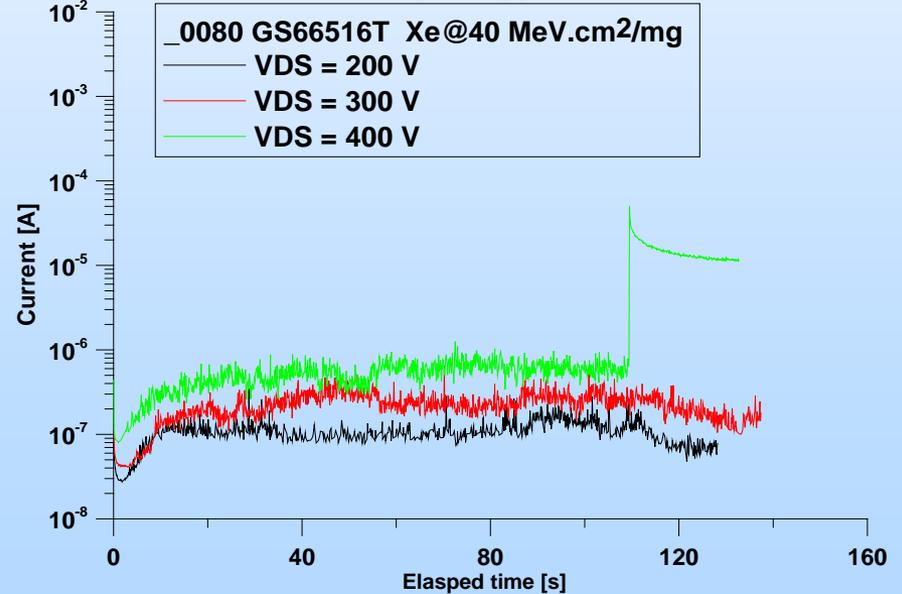
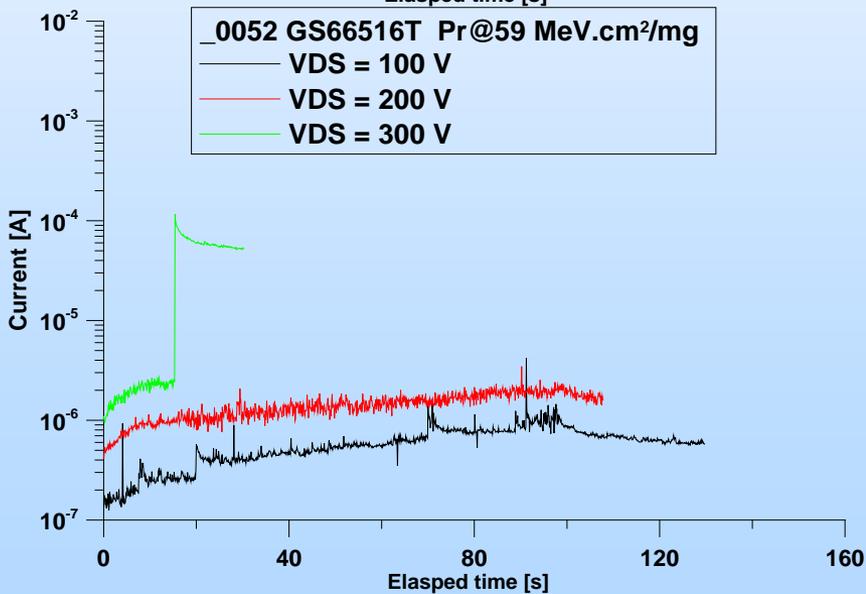
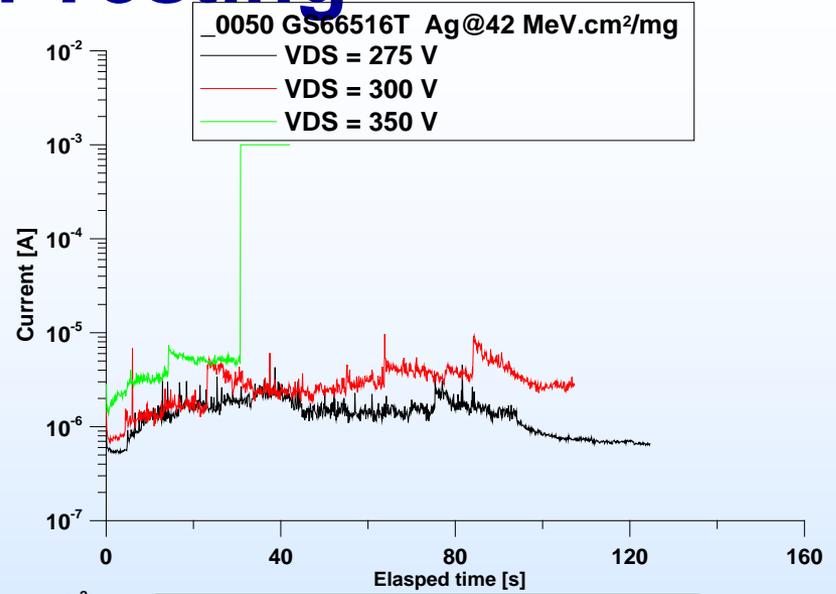
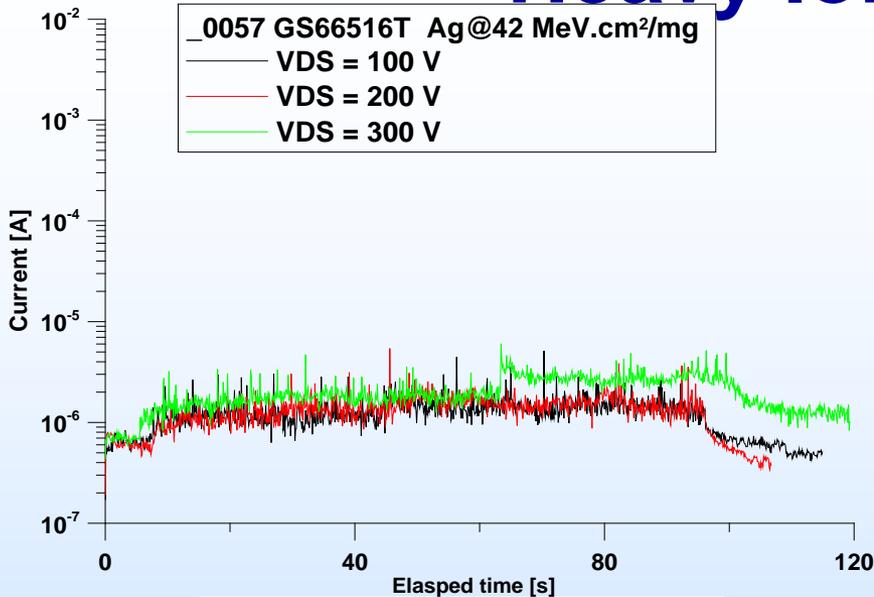


Active contact

Gate areas are small and more complex in newer devices.

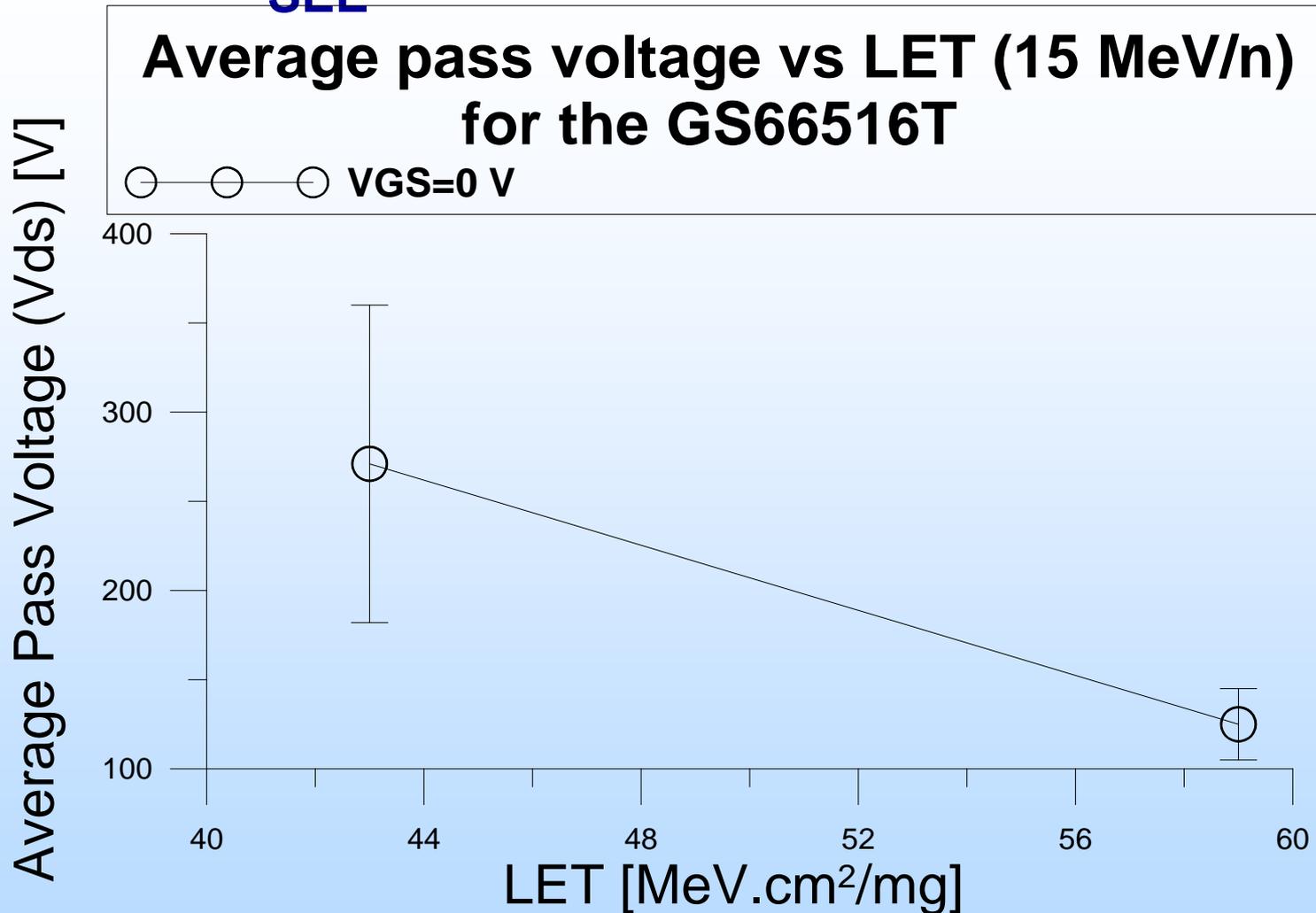


Heavy Ion Testing





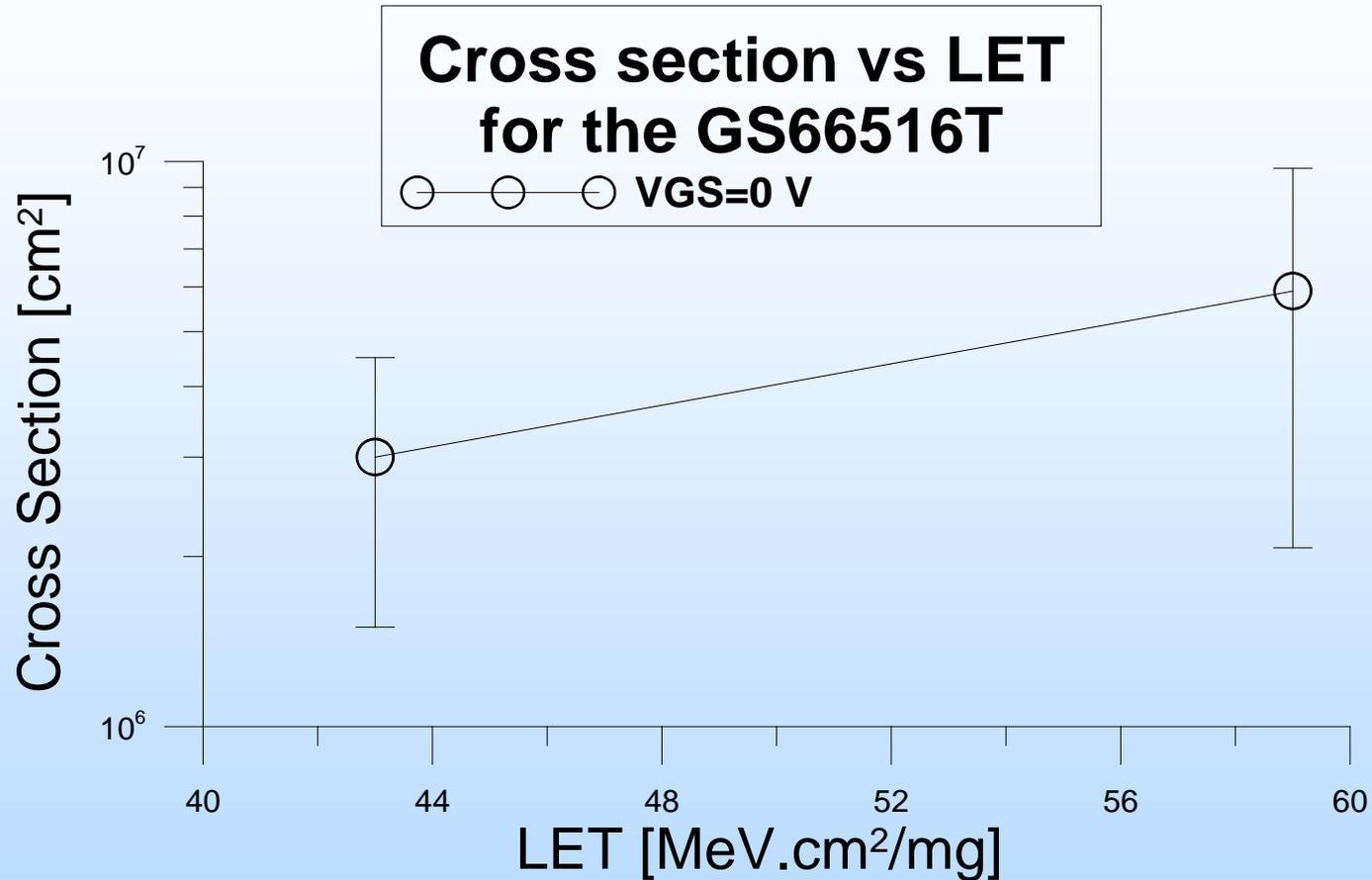
V_{SEE} as a function of LET



Preliminary: Higher LET results in lower SEE Vds.



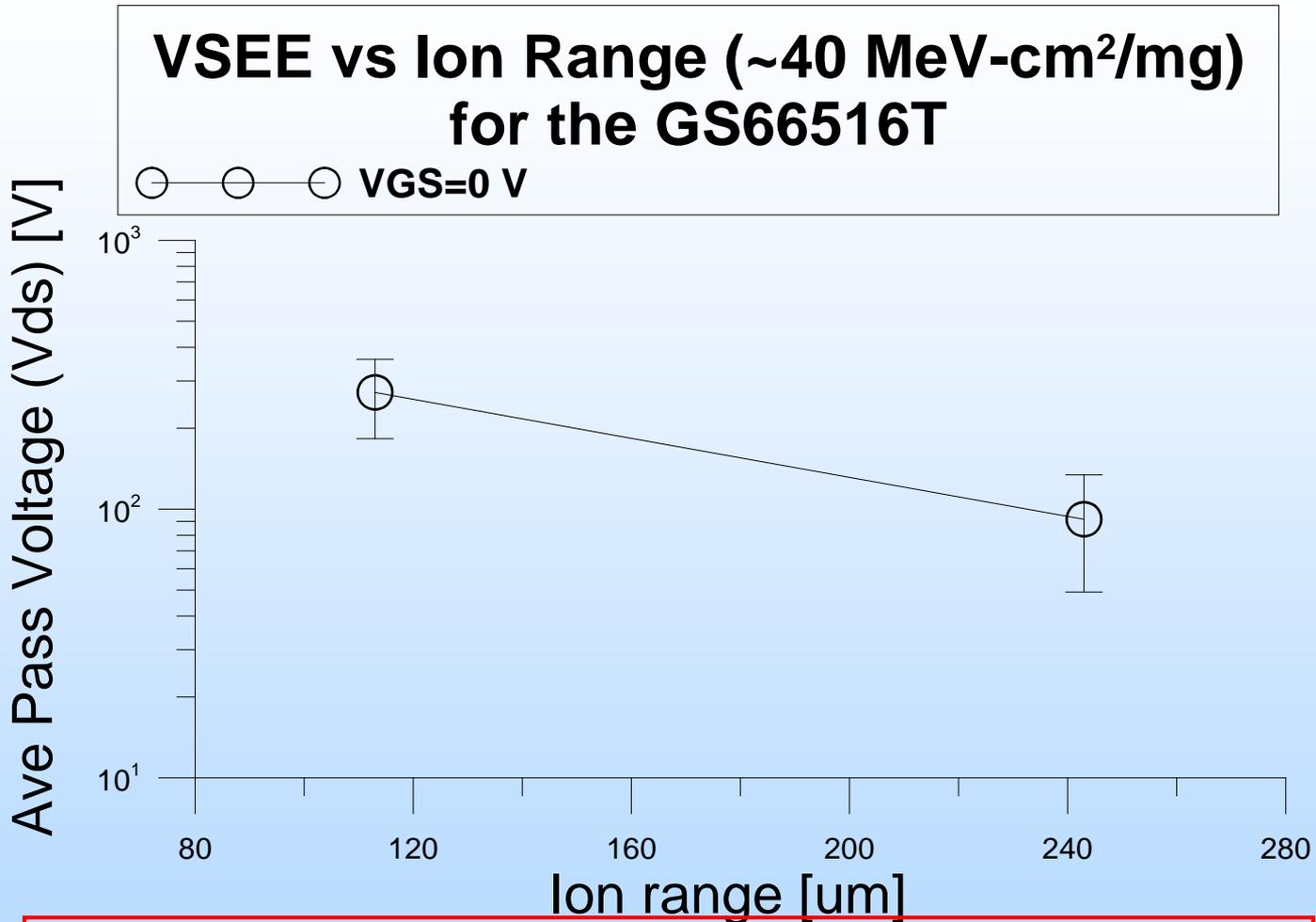
Cross-section as a function of LET



Preliminary: Cross-section not dependent on LET.



V_{SEE} as a function of ion range



**Preliminary: Longer range ions are more damaging
Xe versus Ag.**



FUTURE WORK

To be presented at the 7th NASA Electronic Parts and Packaging (NEPP) Program Electronic Technology Workshop June 16, 2016,
NASA GSFC, Greenbelt, MD.

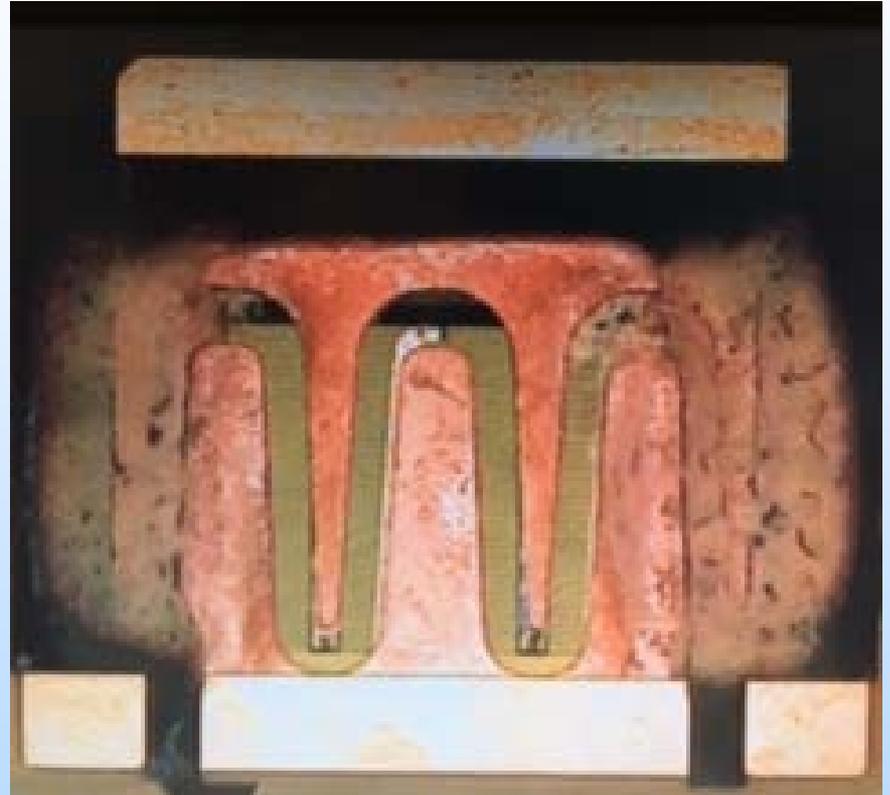
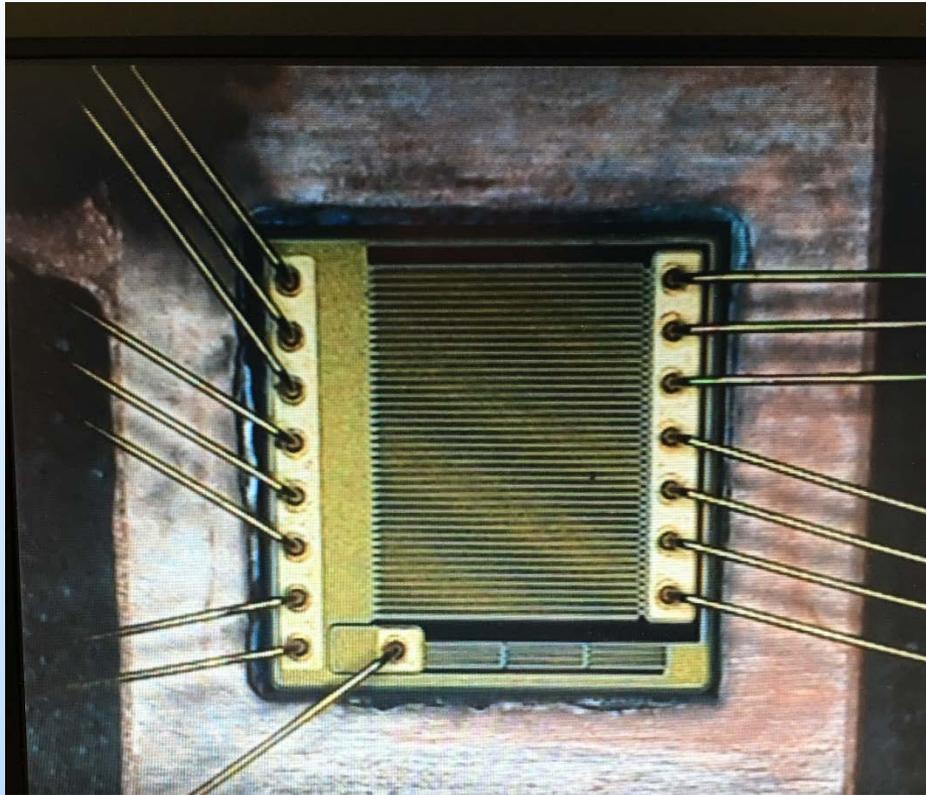


More testing...

- **Testing of emerging parts**
 - GaNSystems
 - Freebird Semi
 - Panasonic
 - Northup Grumman
- **Collaboration with other entities**
 - NASA
 - DOE and DOD
 - Vendors

More GaN devices are becoming available every day.

EMMI and IR SEE site recovery



This will identify SEE location to establish trends
and identify mechanism.

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NASA GSFC, Greenbelt, MD.



Conclusion

- **SEE in GaN HEMTs are complex**
 - Mechanisms and underlying device physics are still under study
- **New devices show similar effects**
 - Panasonic parts seem more robust
 - GaNSystems have more complicated SEE response
- **Future plans**
 - Measurement of LRC circuit in testers
 - Development of an SOA
 - High voltage issues are becoming more visible
 - Continual search for GaN IGFET